IN THE CLAIMS

- (Previously Presented) A process for immobilizing nucleic acid molecules on a substrate, comprising the steps of:
- a) treating said substrate with atomic oxygen plasma prior to immobilizing said nucleic acids; and
- b) immobilizing said nucleic acid molecules on said treated substrate, wherein said substrate is a single crystal surface or an amorphous surface selected from the group consisting of silicon oxides, aluminum oxides, sapphire, perovskites, and derivatives and stabilized and/or doped derivatives thereof.
- 2. (Previously Presented) The process according to claim 1, wherein the nucleic acid is selected from the group consisting of DNA, RNA, PNA, CNA, RNA, HNA, p-RNA, oligonucleotides, oligonucleotides of DNA, oligonucleotides of RNA, primers, A-DNA, B-DNA, Z-DNA, polynucleotides of DNA, polynucleotides of RNA, T-junctions of nucleic acids, domains of non-nucleic acid polymer-nucleic acid blockpolymers and combinations thereof.
- (Previously Presented) The process according to claim 1, wherein the nucleic acid is double-stranded or single-stranded.
- 4. (Previously Presented) The process according to claim 1, wherein the nucleic acid is of natural character, modified, such as substituted with functional groups, nonmodified or artificially generated.

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oxygen from an oxygen gas or from a mixture of gases containing oxygen is used.					
į.	9.	(Cancelled).			
	10.	(Previously Presented)	The process according to claim 1, wherein the		
atomic oxygen plasma treatment is carried out using an oxygen pressure in the range of about 0.1					
to 1.0 mbar.					
	11.	(Previously Presented)	The process according to claim 1, wherein the		
nucleic acid to be immobilized on the substrate is present in an aqueous solution.					

3

microwave generated oxygen plasma producing atomic oxygen from an oxygen gas or from a

voltage generated and/or UV-light emitting source generated oxygen plasma producing atomic

The process according to claim 1, wherein

The process according to claim 1, wherein high-

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(Cancelled).

(Cancelled).

mixture of gases containing oxygen is used.

(Previously Presented)

(Previously Presented)

The process according to claim 11, wherein the

substrate is treated with said aqueous solution for about a few seconds to about 5 minutes.					
. 13.	(Cancelled).				
14.	(Cancelled).				
15. perovskites	(Previously Presented) are selected from the group cou	The process according to claim 1, wherein the nsisting of SrTiO ₃ , LaAlO ₃ and ZrO ₂ .			
16.	(Previously Presented)	The process according to claim 10, wherein the ar.			

(Previously Presented)

12.

18. (Previously Presented) The process according to claim 1, wherein the substrate is treated with atomic oxygen plasma for about 0.1 to 10 minutes.

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